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gas injection assembly making at least one of said first and second gases into the gas plasma for injecting into said processing chamber.

76. (New)

A manufacturing method for a semiconductor device according to Claim 75, wherein said first gas includes ammonia, the making at least one of said first and second gases into the gas plasma includes making said first gas into the gas plasma, and said second gas includes silane.

77. (New)

A manufacturing method for a semiconductor device according to Claim 76, wherein said second gas is injected into said processing chamber without being made into the gas plasma.

REMARKS

An early and favorable action on the merits is respectfully solicited.

Respectfully submitted,

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By: Van Dyke, Gardner, Linn & Burkhart, LLP

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Date

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